



#11/C1765
PATENT
3/16/03

Customer No. 22,852
Attorney Docket No. 07553.0009

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
Michiaki SANO) Group Art Unit: 1765
Serial No.: 09/671,201) Examiner: L. Vinh
Filed: September 28, 2000)
For: PLASMA PROCESSING)
METHOD)

Assistant Commissioner for Patents
Washington, DC 20231

Sir:

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AMENDMENT

In reply to the Office Action dated October 3, 2002, the period for reply having been extended for one month by a request for extension and fee payment filed concurrently herewith, please amend the application as follows:

IN THE CLAIMS:

Please cancel claims 10-28 and 38-40 without prejudice or disclaimer, amend claim 32, and add new claims 41-62, as follows:

32. (Amended) A plasma processing method comprising:
- etching a film by utilizing a resist film as a mask;
 - ashing the film with a first high-frequency biasing power level substantially halfway through the resist film, after etching; and

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